

Supporting Information

Formation of Surface Relief Gratings with Homeotropically Oriented Photopolymer from a Photocross-Linkable Organic Monomer

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Synthetic procedures

n-Propyldiphenylacetylenecarboxylic acid benzyl ester, PDABE

To a solution of benzyl alcohol (1.08 g), 4-(2-(4-propylphenyl)ethynyl)benzoic acid (synthesized in our laboratory, 2.64g) and 4-Dimethylamino-pyridine (DMAP, 0.05 g) in CH₂Cl₂ (120 mL) was added slowly in a solution of DCC (2.06 g) in CH₂Cl₂ (5 mL) at 0 °C. The mixture was allowed to warm up to room temperature and overnight, then concentrated. The residue was purified by column chromatography (silica gel, dichloromethane) to give PDABE (yield 2.97 g, 83.8 %) as a white solid. PDABE mp: 76-77 °C. ¹H NMR (400 MHz, CDCl₃): δppm 0.94 (t, J = 7.2 Hz, 3H, -CH₃), 1.57 (m, J = 8.0 Hz, 2H, -CH₃CH₂CH₂), 2.61 (t, J = 7.6 Hz, 2H, -CH₃CH₂CH₂), 5.38 (s, C₆H₅-CH₂-, 2H), 7.18 (m, J = 8.0 Hz, 2H, Ar-H), 7.36 (t, J = 6.8 Hz, 5H, Ar-H), 7.46 (t, J = 8.0 Hz, 2H, Ar-H), 7.52 (m, J = 8.4 Hz, 2H, Ar-H), 8.05 (d, J = 8.4 Hz, 2H, Ar-H).

n-Propylbiphenylcarboxylic acid cinnamyl ester, PBACE

To a solution of cinnamyl alcohol (1.34 g), 4-Propylbiphenylcarboxylic acid (synthesized in our laboratory, 2.70 g) and DMAP (0.05 g) in CH₂Cl₂ (120 mL) was added slowly in a solution of DCC (2.11 g) in CH₂Cl₂ (5 mL) at 0 °C. The mixture was allowed to warm up to room temperature and overnight, then concentrated. The residue was purified by column chromatography (silica gel, dichloromethane) to give PBACE (yield 2.76 g, 77.6 %) as a white solid. ¹H-NMR (400 MHz, CDCl₃): δppm 0.94 (t, J = 7.6 Hz, 3H, -CH₃), 1.65 (m, J = 7.2 Hz, 2H, -CH₃CH₂CH₂), 2.63 (t, J = 7.6

Hz, 2H, -CH₃CH₂CH₂), 5.01 (t, J = 5.8 Hz, -COOCH₂-, 2H), 6.40 (m, J = 6.4 Hz, Ar-CH=CH-, 1H), 6.75 (d, J = 15.6 Hz, Ar-CH=CH-, 1H), .26 (m, J = 6.4 Hz, 5H, Ar-H), 7.43 (t, J = 7.2 Hz, 2H, Ar-H), 7.55 (d, J = 8.0 Hz, 2H, Ar-H), 7.65 (m, J = 8.0 Hz, 2H, Ar-H), 8.13 (d, J = 8.4 Hz, 2H, Ar-H).

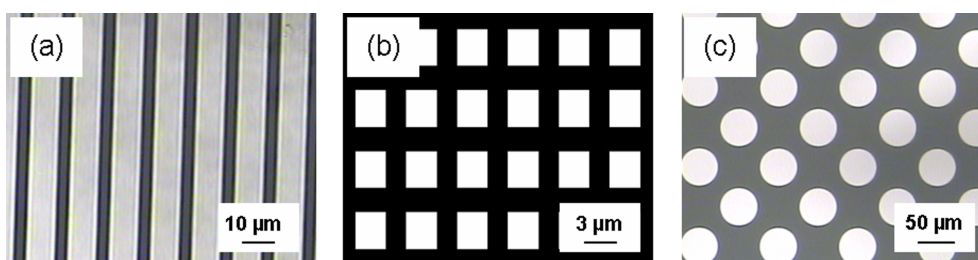


Figure S1. Photographic images of the photomasks used in this study. (a) the striped mask (the exposed width is 10 μm and the shaded width is 5 μm); (b) the grid-type mask (the exposed width is 3 μm and the shaded width is 2 μm) and (c) the circular mask (the exposed diameter is 50 μm and the shaded width is 25 μm).

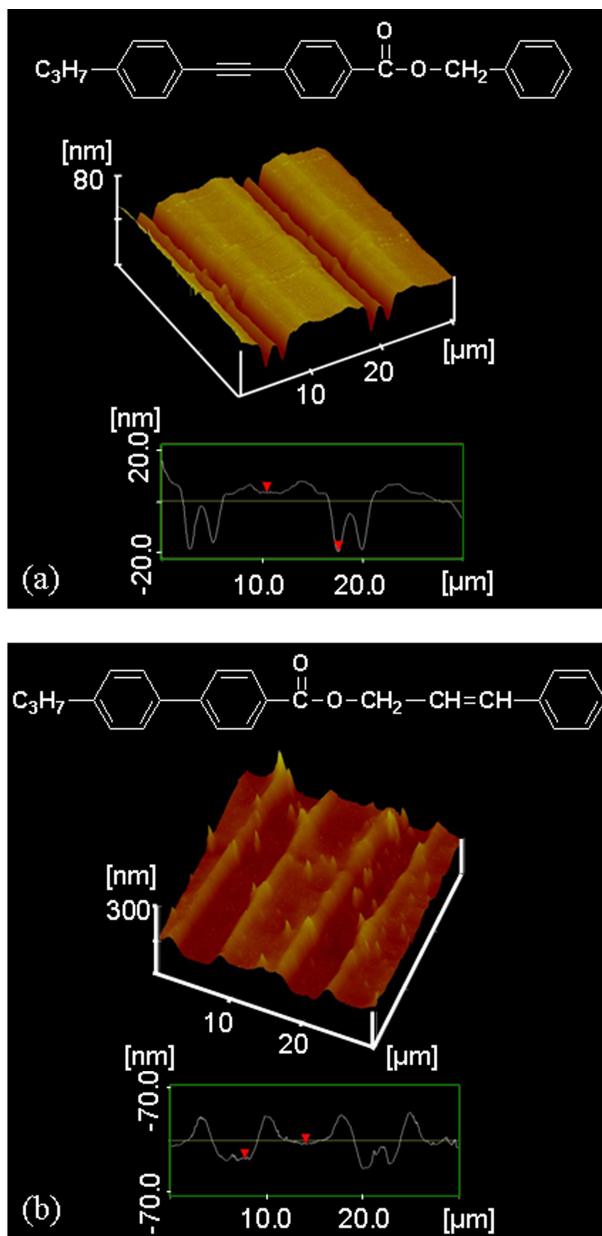


Figure S2. Chemical structures of the monomers PDABE and PBACE and the AFM images of their photoirradiated films under the striped mask. (a) PDABE, irradiated with 365.0 nm UV light (6.5 mW/cm^2 , 60.0 s). (b) PBACE, irradiated with 365.0 nm UV light (35.0 mW/cm^2 , 60.0 s).

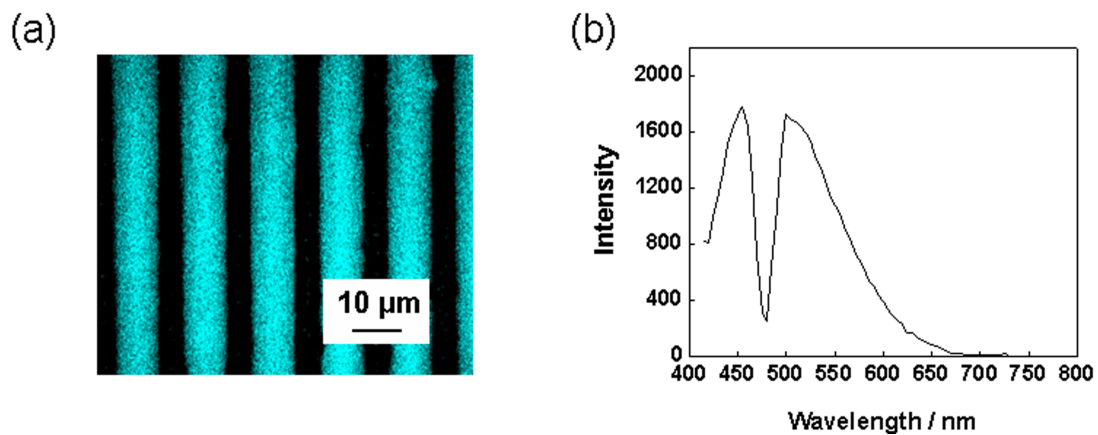


Figure S3. (a) Confocal image of the striped SRG. (b) Fluorescent emission spectra of the photocross-linked polymer of the striped SRG excited at 405 nm.